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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/748,345	12/29/2003	Mark L. Doczy	42P17820	8139
59796 INITEL CORD	7590 11/29/2007 OP A TION		EXAM	INER
INTEL CORPORATION c/o INTELLEVATE, LLC			THAI, LUAN C	
P.O. BOX 52050 MINNEAPOLIS, MN 55402			ART UNIT	PAPER NUMBER
2×222 12 1 2 1 22 0 =	,		2891	
			MAIL DATE	DELIVERY MODE
			11/29/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

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	Application No.	Applicant(s)				
Office Action Summers	10/748,345	DOCZY ET AL.				
Office Action Summary	Examiner	Art Unit				
The MAILING DATE of this course is all	Luan Thai	2891	_			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet t	with the correspondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period v - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUN 36(a). In no event, however, may will apply and will expire SIX (6) MO c, cause the application to become	AICATION. a reply be timely filed DNTHS from the mailing date of this communication. ABANDONED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 31 O	<u>ctober 2007</u> .					
2a) This action is FINAL . 2b) ⊠ This	This action is FINAL . 2b)⊠ This action is non-final.					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in accordance with the practice under E	Ex parte Quayle, 1935 C	D. 11, 453 O.G. 213.				
Disposition of Claims						
4) ⊠ Claim(s) <u>1,2,4-8,11-13,15,16 and 25</u> is/are per 4a) Of the above claim(s) is/are withdraw 5) □ Claim(s) is/are allowed. 6) ⊠ Claim(s) <u>1-2, 4-8, 11-13, 15-16 and 25</u> is/are re 7) □ Claim(s) is/are objected to. 8) □ Claim(s) are subject to restriction and/or	wn from consideration.					
Application Papers		•				
9) The specification is objected to by the Examine	er.					
10)☐ The drawing(s) filed on is/are: a)☐ acce		o by the Examiner				
Applicant may not request that any objection to the	•	•				
Replacement drawing sheet(s) including the correct	ion is required if the drawir	g(s) is objected to. See 37 CFR 1.121(d).				
11)☐ The oath or declaration is objected to by the Ex	aminer. Note the attach	ed Office Action or form PTO-152.				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in rity documents have bee u (PCT Rule 17.2(a)).	Application No en received in this National Stage				
Attachment(s)						
1) Notice of References Cited (PTO-892)		Summary (PTO-413)				
Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date		o(s)/Mail Date f Informal Patent Application 				
S. Patent and Trademark Office	·		_			

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DETAILED ACTION

Request for Continued Examination

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 10/31/07 has been entered.

Claims 1-2, 4-8, 11-13, 15-16 and 25 are pending in this application.

Claims 3, 9-10, 14 and 17-24 have been cancelled.

Claim Objections

1. Claim 6 is objected to under 37 CFR 1.75 as being a substantial duplicate of claim 1. When two claims in an application are duplicates or else are so close in content that they both cover the same thing, despite a slight difference in wording, it is proper after allowing one claim to object to the other as being a substantial duplicate of the allowed claim. See MPEP § 706.03(k).

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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3. Claims 1-2, 4-8, 11-13, 15-16 and 25, are rejected under 35 U.S.C. 103(a) as being unpatentable over Chambers (7,005,365 of record) in view of Goto (6,599,819 of record).

Regarding claims 1-2, 4-8, 11-13, 15-16 and 25, Chambers disclose (see specifically figures 1-3, Col. 2, line 62 to Col. 8, line 45) a method of forming a microelectronic structure comprising: providing a substrate (110/210) comprising source/drain regions (155/160, 255/260) and gate region there between, wherein the gate region comprises a metal gate electrode (125/135, 225/235) of ruthenium, palladium, or platinum (Col. 6, lines 28+ and Col 8, lines 22+) disposed as a single layer and directly disposed on a high k gate dielectric layer (105/205) of hafnium dioxide (Col. 4, lines 58+), a spacer (165/265) being in direct contact with the metal gate electrode (125/135, 225/235); laser annealing the substrate to activate the implanted species; a doped polysilicon fill layer (295) may disposed on the metal gate electrode (225/235). Since the doped polysilicon fill layer, which is disposed on the metal gate electrode, is commonly applied in the art as a protective layer for the metal gate electrode (as evidenced by Fuse et al., U.S. Patent No. 4,629,286, Col. 4, lines 25+, of record), the metal gate electrode is obviously considered "not substantially diffuse into the polysilicon fill layer". Chambers further discloses NMOS gate electrode and a PMOS gate electrode (Col. 1, lines 22+ and Col 6, lines 10+), and the metal gate layer can be selected to have the work function in the range from about 4 electron volts to about 4.2 electron volts and from about 5 electron volts to about 5.2 electron volts (Col. 6, lines 13+). Chambers, thus, discloses the claimed invention as detailed above except for specifying the laser beam pulsed at about 20 nanoseconds or less.

Although Chambers does not specify the claimed time range of the laser beam pulsed (e.g., 20 nanoseconds or less), the annealing time using laser beam is commonly less than 20 ns

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for activating the implanted regions in a substrate, as disclosed by Goto (Col. 3, lines 49+). It would have been obvious to one of ordinary skill in the art at the time the invention was made to pulse the laser beam to the substrate at about 20 ns or less for activating the implanted regions in the substrate since such the pulsed time of a laser beam is commonly applied in the art, as taught by Goto, and such time range is an art recognized variable of importance which is subject to routine of experimentation and optimization.

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4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Luan Thai whose telephone number is 571-272-1935. The examiner can normally be reached on 8:00 AM - 4:30 PM, Monday to Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Bradley W. Baumeister can be reached on 571-272-1722. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Luan Thai

Primary Examiner Art Unit 2891

November 23, 2007